

Reactive Magnetron Sputter System

Model: SA-VKV550

SA-VKV550 is an ion-source-enhanced reactive magnetron sputtering system. It delivers superior film quality, features a highly automated control system and low-maintenance design, and satisfies R&D and small-batch-production requirements for enterprises and research institutes.



Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

Application

- Laser
- R&D
- Integrated circuit
- MEMS

Specifications:

Parameter	Descriptions
Number of Cathodes	2(max.)
Sputtering Power Supply	DC / RF / pulsed DC, freely switchable
Ion Source	RF & Kaufman & Hall ion source
Bias	RF / pulsed DC
Vacuum Sampling Chamber	Single-wafer/multi-wafer fully-automatic sampling chamber, optional
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Flow Control	Digital mass flow meter
Coating Uniformity	±2%
Coating Repeatability	±2%
Uniform Deposition Area	Ø200 mm(max.)
Ultimate Vacuum	1E-5Pa
Vacuum Measurement	Full-range vacuum gauge + Capacitance diaphragm gauge
Temperature Control Range	-50~800℃
Space Requirements(L×W×H,m)	3.8×2.8×2.2

Principle:

